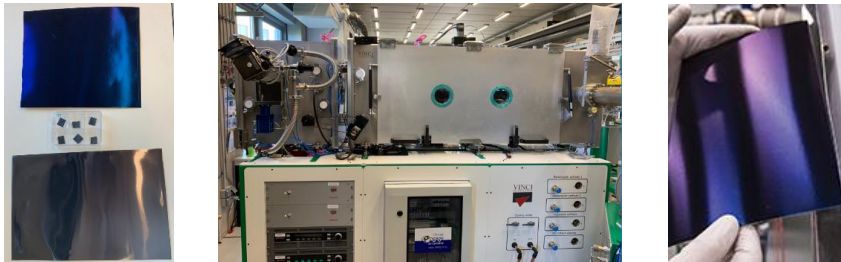


Our Services

Thin film elaboration using a large sputtering machine (A4 scale)



YOUR NEEDS

- Innovate and develop new thin films (oxide or metallic)
- Coating elaborated by magnetron sputtering homogeneous in composition and thickness over a large area
- Ready for all type of flat substrate

RELATED SKILLS

- Deposition under ultra high vacuum (ALD – PLD – MBE)
- Material structuration
- Growth of nanomaterials
- Chemical characterization (Spectroscopies, etc.)
- Structural characterization :
 - Electron microscopy (SEM – TEM)
 - X-ray diffraction
 - Atomic force microscopy (AFM)

OUR SOLUTIONS

Magnetron sputtering machine capable of accommodating A4 format planar substrates.
2 large flat magnetrons (40*6cm)
Deposition can be done in metallic and reactive mode (nitrogen and/or oxygen)
Switching room allowing rapid substrate rotation
Provide our skills and characterization devices to support you in your innovation process

OUR REFERENCES



KEYWORDS

Thin films, PVD, sputtering, characterization of thin films, metallic, reactive, large area, homogeneous

CONTACT

- Contact the research group:
 -  jean-francois.pierson@univ-lorraine.fr
 -  +33 3 72 74 25 99
 -  fabien.capon@univ-lorraine.fr
 -  +33 3 72 74 25 96
- Contact the technology transfer office (TTO):
 -  ijl-tto@univ-lorraine.fr
 -  +33 3 72 74 26 04